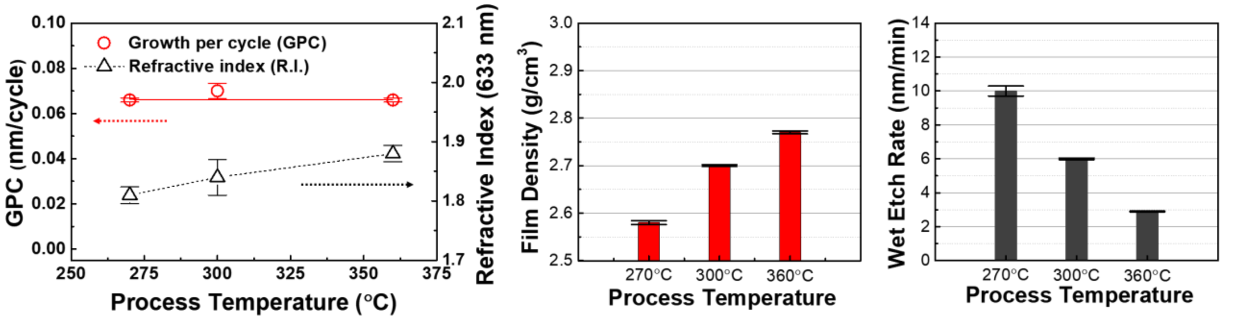
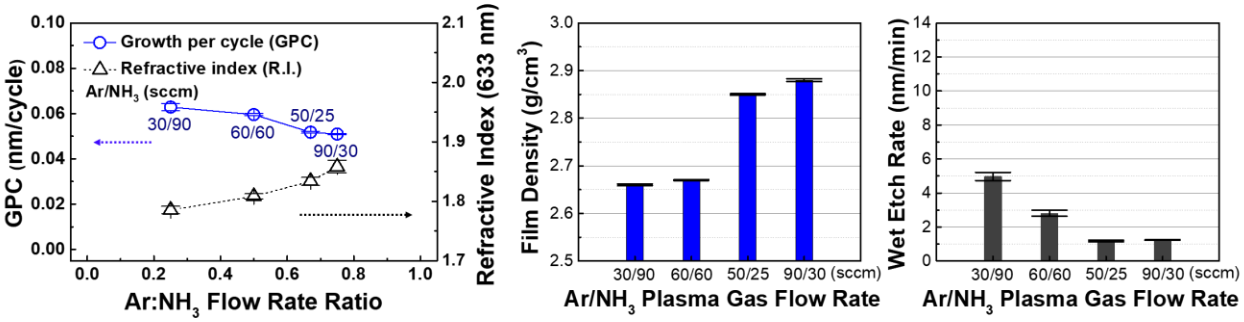


(a) (b) (c)

Figure 1. Evaluation of (a) GPC, and R.I., (b) film densities, and (c) WER at process temperatures of 270°C, 300°C, and 360°C under constant plasma gas composition of N_2/NH_3 30/90 sccm.



(a) (b) (c)

Figure 2. Evaluation of (a) GPC, and R.I., (b) film densities, and (c) WER at Ar/NH_3 plasma gas composition of 30/90, 60/60, 50/25, 90/30 sccm under constant process temperature of 300°C.

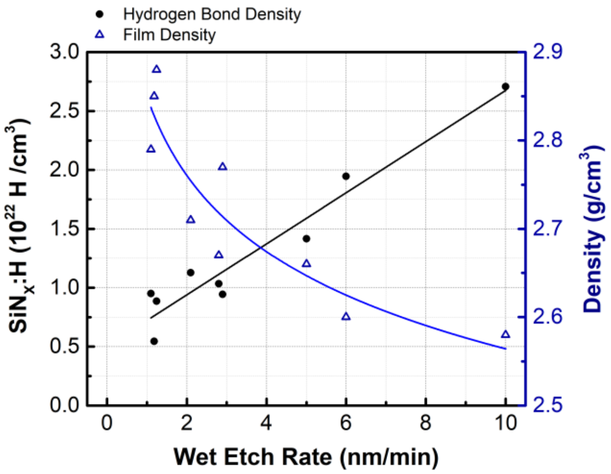


Figure 3. The correlation between WER, hydrogen bond density extracted from FT-IR peak absorbance, and bulk film density from XRR is plotted from 9 different PEALD processes.